

ABSTRACT OF THE DISCLOSURE

The present invention relates to a novel light absorbent for forming an organic anti-reflective layer, which is a ring-opened phthalic anhydride compound, an organic anti-reflective layer composition, a method for patterning a semiconductor device using the organic anti-reflective layer composition, and a semiconductor device produced by the method for patterning.

An anti-reflective protective layer formed using the compounds of the present invention exhibits excellent adhesiveness and storage stability, as well as excellent resolution in both C/H patterns and L/S patterns. The anti-reflective protective layer also has an excellent process window, so that excellent pattern profiles can be obtained irrespective of the type of the substrate.

FIG. 1